

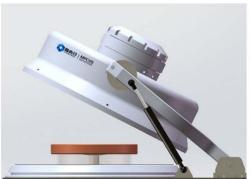
#### Let there be no difficult diamond manufacturing in the world

# 上海顺心谷半导体科技有限公司



Shanghai Shunxingu Semiconductor Technology Co., Ltd.









Determined to become the No.1 MPCVD supplier in China



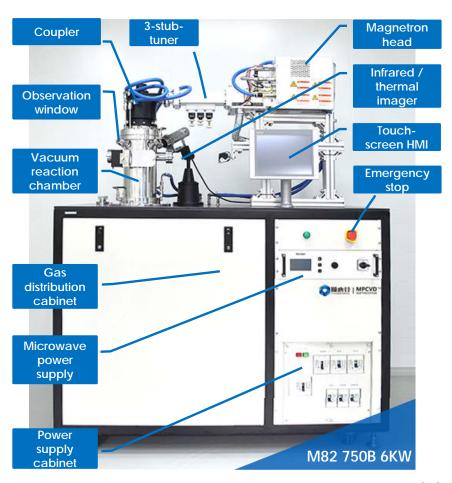
## Introduction M82 750B 6KW

- Designed with profound engineering skills to make sure that cutting edge technologies are made available to our valued customers
- Extremely stable operations and outstanding cost-efficiency
- All components are carefully selected and/or processed with great precision
- During the assembly, stringent and multi-level test procedures are rigorously carried out with zero tolerance for flaws
- To ensure a safe and productive operation, a distinguishing user-friendly program interface with various applications and protection mechanisms was established
- Customers applying M82 750B 6K are rewarded with a quality of synthetized diamonds which can repeatably fulfill the F, E and under circumstances even D color classes.





#### **Device Parameters**



Item	Data
Device model	M82 750B 6KW
Power supply	AC380V±10% 50Hz
Operating system	SXG-MPCVD Control System
Microwave Source	Muegge 2450MHz/6KW
Chamber nominal power	10 KW
Substrate size	Φ 2 inches
Working pressure	10-200 Torr
Standardized gas configuration	5-6 gas lines (can be customized)
Temperature measurement	Infrared or thermal imaging measurement; temperature range: 300~1400 ℃
System vacuum tightness (leak detection by helium mass spectrometer)	<1×10 <sup>-9</sup> Torr·L/sec
Vacuum pump	17.1 m <sup>3</sup> /h
Monocrystalline growth rate	10-15 μm/h (acc. to customer reference)
Equipment dimension	1500mm(length)* 800mm(depth)* 1980mm(height)
Equipment weight	490 kg

### Highlights

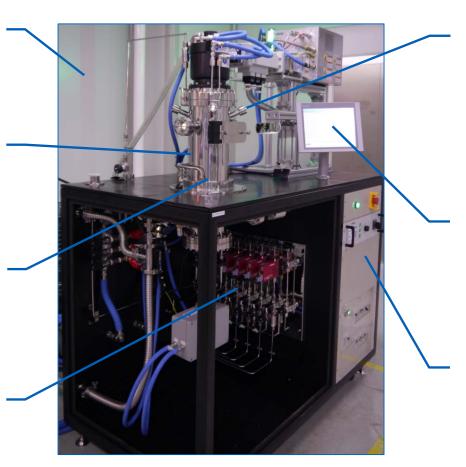
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High precision and integration level of the equipment, high space utilization

Optimized cavity and adapter design by means of field simulation, enhancing growth efficiencies

Precisely temperaturecontrolled water-cooled reaction chambers and automatically real-time adjustable growth substrate

High-precision process-gas flow control enables longtime and stable operations



Upon customer's requirements, it's optionally available to monitor the temperature field within the reaction chamber with a thermal imaging camera

Flexible automatic/manual switching operation and extensive data logging capabilities

Imported microwave system from Europe with high output energy density within which the plasma ball can maintain a high degree of stability



### **Contact us**

